E-beam deposition evaporator system

Manufacturer: **Tectra**

Model: Spuca

Description:

Tectra Spuca has been designed for E-beam and RF sputtering deposition of metals (especial for the metal with high melting point temperature). The system combines one E-beam source and one RF sputtering source in the chamber. The metals include: Au, Ag, Al, Cu, Fe, Pt, SiO₂ etc.

Specification

Name	Function
Sputter Coater	High-vacuum deposition-system, Vacuum degree: 10^{-6} - 10^{-7} Torr
	Stainless steel sputter chamber (diameter 300mm) with a large access door (300mm, incl. viewport)
	Turbo pump with auto-venting valve and membrane roughing pump
	Compact full range pressure gauge
	Mounted in 19" rack, can be mobile
2" Magnetron Sputter Gun	Internally mounted. Water-cooled
	Magnetron power supply
	250W RF, as above but with automatic matching network and control panel
Bakeable Leak Valve	For gas inlet for sputtering systems, bakeable to 450°C (Opened or Closed)
eFlux	e-beam heated crucible evaporator, ca. 0.25cc - including power supply, control options and other options on request, additional port is necessary
Source Shutter	Manually operated for boats, magnetrons, e-beam evaporators etc.
Quartz Microbalance	One thickness and rate controller
System	- Thickness range: 0.0 nm to 999.9 μm
	- Thickness resolution: 0.1 nm

	 Rate of deposition range: 0.0 nm/s to 999.9 nm/s Relay output e.g. for shutter control at given thickness Analogue output of thickness or rate: 0-1 volt Sampling rate varies automatically: 1 Hz to 4 Hz Film parameters recordable in 8 material memory (density, tooling factor, z- value) One sensor head, side mount, CF-35 rotatable, water-cooling One oscillator and cable set
Residual Gas Analyzer	With Saddle Mounted Mass Filter
	PC Controlled RGA via RS232 (PC not included)
	Mass Range 2- 200amu.
Plasma Cleaning of the Chamber	Include low DC power supply
Additional Ports,	Adapter, from NW16CF to 1/4" Swagelok, ×1
Adapters and	Dowt NIN/25C5 (OD 2.75") v1
Accessories	Port, NW35CF (OD 2.75"), ×1
	DV-158 back to air valve, ×1, gas inlet for sputtering systems

